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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of

Applicant Patricia B. Smith, et al.

Docket Number: TI-29811

Serial No.: 09/975,639

Art Unit: 2818

Filed: 10/11/01

Examiner: Quoc D. Hoang

For: Hydrogen Plasma Photoresist Strip and Polymeric Residue  
Cleanup Process for Low Dielectric Constant Materials

**CERTIFICATION OF FACSIMILE TRANSMISSION**

I hereby certify that the following papers are being transmitted by facsimile  
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5-26-05  
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<input type="checkbox"/> <b>CONTINUATION APP'N</b>	<input checked="" type="checkbox"/> <b>ELECTION</b>
<input type="checkbox"/> <b>DIVISIONAL APP'N</b>	
<b>NAME OF INVENTOR(S):</b> Patricia B. Smith, et al.	
<b>TITLE OF INVENTION:</b> Hydrogen Plasma Photoresist Strip and Polymeric Residue Cleanup Process for Low Dielectric Constant Materials	
<b>TI FILE NO.:</b> <b>TI-29811</b>	<b>DEPOSIT ACCT. NO.:</b> <b>20-0668</b>
<b>FAXED:</b> 5-26-05 <b>DUE:</b> 6-12-05 <b>ATTY/SEC'Y:</b> RAK/kjv	
<b>RECEIPT DATE &amp; SERIAL NO.:</b> <b>Serial No.: 09/975,639</b> <b>Filing Date:</b> 10/11/01	

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Docket No.: TI-29811

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Examiner: Hoang, Quoc

Title: Hydrogen Plasma Photoresist Strip and Polymeric Residue Cleanup Process for Low Dielectric Constant Materials

ELECTION

May 26, 2005

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22131-1450

Dear Sir:


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Karen Vertz

In response to the Examiner's restriction requirement dated 05/12/05, following the submission of the Appeal Brief in the above-identified patent application, this election is offered. The Applicants provisionally elect, with traverse, to pursue Claims 1, 5-13, 30-39, and 60-68. In addition, the Applicants request reconsideration and withdrawal of the Examiner's restriction requirement. Reconsideration and withdrawal is respectfully requested because the classification and field of search is the same regardless of whether the inventive residue removal step is performed with the advantageously claimed wet or dry processes. Therefore, even though the first and second embodiments are patentable over each other, no reason exists for concluding that each embodiment has attained recognition in the art as a separate status or field of search.

Respectfully submitted,

  
Rose Alyssa Keagy  
Attorney for Applicants  
Reg. No. 35,095

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